

Title (en)

METHOD AND INSTALLATION FOR REDUCING ELEMENTARY HALOGEN IN A GASEOUS EFFLUENT

Title (de)

VERFAHREN UND VORRICHTUNG ZUR VERRINGERUNG VON ELEMENTAREN HALOGENEN IN ABGASEN

Title (fr)

PROCEDE ET INSTALLATION DE REDUCTION DE L'HALOGENE ELEMENTAIRE DANS UN EFFLUENT GAZEUX

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Application

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Abstract (en)

[origin: WO0141903A1] The invention relates to a method for reducing the elementary halogen contained in a gaseous effluent from a combustion furnace for combusting halogenated residues, comprising the bringing of said effluent into contact with hydrazine. The invention also relates to a device or an installation for treating a gaseous effluent from a combustion furnace (1) for combusting halogenated residues, comprising a unit (6, 10, 14) in which the gases are brought into contact with an aqueous solution of hydrazine. Finally, the invention relates to a solution of halohydric acid containing hydrazine.

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